

**MOVABLE-BODY APPARATUS, EXPOSURE APPARATUS,
EXPOSURE METHOD, AND DEVICE MANUFACTURING METHOD**

ABSTRACT

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A moving grating (30X) is arranged on a side of a wafer stage (WST), a light source (22) irradiates a light to the moving grating, diffracted lights generated from the moving grating are interfered by fixed scales (24A, 10 24B) and an index scale (26) of which positional relation with the light source is fixed, and a detection instrument (28) detects the interfered light. In this case, since the moving grating is arranged on a side of the wafer stage, upsizing of the entire wafer stage can be suppressed. 15 Further, since interference occurs between a plurality of diffracted lights (e.g., the ± 1 st-order diffracted light) passing extremely close optical paths, influence caused by a fluctuation of ambient atmosphere becomes less in comparison to conventional 20 interferometers, and thus, a high-precision measurement of positional information of the movable body is possible.

Figure 2

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